

L Number	Hits	Search Text	DB	Time stamp
1	162	430/311-313,394.ccls. and (interlac\$ or intertwin\$ or double adj expos\$)	USPAT; US-PGPUB; JPO	2003/02/10 18:03
2	1	430/311-313,394.ccls. and (interlac\$ or intertwin\$ or double adj expos\$)	EPO; DERWENT; IBM_TDB	2003/02/10 18:15
5	4	(((((photoresist or resist or photopolymer\$7) and (etch or etched or etching or etchant) and ((doubl\$3 or plural\$4) same expos\$) same (perpendicular\$3 or cross\$3 or interlac\$3 or intertwin\$3 or row or column)) and semiconduct\$3 and (stor\$3 or capacit\$4 or memor\$5)) and ((line\$2 or parallel) same expos\$3)) and develop\$4) and (dynamic adj random adj access or DRAM or memory)) and ((round\$3 with corner) or (optical with proximity) or (line with short\$5))) and 430/312.ccls.	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/02/10 18:21
6	2	(((((photoresist or resist or photopolymer\$7) and (etch or etched or etching or etchant) and ((doubl\$3 or plural\$4) same expos\$) same (perpendicular\$3 or cross\$3 or interlac\$3 or intertwin\$3 or row or column)) and semiconduct\$3 and (stor\$3 or capacit\$4 or memor\$5)) and ((line\$2 or parallel) same expos\$3)) and develop\$4) and (dynamic adj random adj access or DRAM or memory)) and ((round\$3 with corner) or (optical with proximity) or (line with short\$5))) and 430/394.ccls.	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/02/10 18:23
7	3	(((((photoresist or resist or photopolymer\$7) and (etch or etched or etching or etchant) and ((doubl\$3 or plural\$4) same expos\$) same (perpendicular\$3 or cross\$3 or interlac\$3 or intertwin\$3 or row or column)) and semiconduct\$3 and (stor\$3 or capacit\$4 or memor\$5)) and ((line\$2 or parallel) same expos\$3)) and develop\$4) and (dynamic adj random adj access or DRAM or memory)) and ((round\$3 with corner) or (optical with proximity) or (line with short\$5))) and 430/313.ccls.	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/02/10 18:24
8	3	(((((photoresist or resist or photopolymer\$7) and (etch or etched or etching or etchant) and ((doubl\$3 or plural\$4) same expos\$) same (perpendicular\$3 or cross\$3 or interlac\$3 or intertwin\$3 or row or column)) and semiconduct\$3 and (stor\$3 or capacit\$4 or memor\$5)) and ((line\$2 or parallel) same expos\$3)) and develop\$4) and (dynamic adj random adj access or DRAM or memory)) and ((round\$3 with corner) or (optical with proximity) or (line with short\$5))) and 430/311.ccls.	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/02/10 18:25
10	331	430/312,394.cor.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/02/10 18:34
12	1717	430/312,394.ccls. not 430/312,394.cor.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/02/10 18:52

13	3071	(430/311-313,394.ccls. not 430/312,394.ccls. not 430/312,394.cor.) and pd>20021204	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/02/10 19:19
14	76	(430/311-313,394.ccls. not 430/312,394.ccls. not 430/312,394.cor.) not @pd<=20021204	USPÄT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/02/10 19:20
-	6	((("5425848") or ("5817242") or ("6027595") or ("5512131") or ("5900160") or ("5925259"))).PN.	USPÄT; US-PGPUB; JPO	2002/10/29 18:38
-	146	430/311-313,394.ccls. and (interlace\$ or intertwine\$ or double adj expos\$)	USPAT; US-PGPUB; JPO	2002/10/21 16:13
-	1	"5604059".PN.	USPAT	2002/10/21 14:40
-	1	430/311-313,394.ccls. and (interlac\$ or intertwin\$ or double adj expos\$)	EPO; DERWENT; IBM_TDB	2003/02/10 18:15
-	146	430/311-313,394.ccls. and (interlac\$ or intertwin\$ or double adj expos\$)	USPÄT; US-PGPUB; JPO	2003/02/10 18:16
-	1	"6042998".PN.	USPAT	2002/10/21 18:09
-	1	"5989952".PN.	USPAT	2002/10/21 18:13
-	1	"5841143".PN.	USPAT	2002/10/21 18:15
-	4951	430/311-313,394.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/02/10 18:17
-	1481	(photoresist or resist or photopolymer\$7) and (etch or etched or etching or etchant) and ((doubl\$3 or plural\$4) same expos\$) same (perpendicular\$3 or cross\$3 or interlac\$3 or intertwin\$3)	USPÄT; US-PGPUB; EPO; JPO; IBM_TDB	2002/11/21 13:23
-	698	((photoresist or resist or photopolymer\$7) and (etch or etched or etching or etchant) and ((doubl\$3 or plural\$4) same expos\$) same (perpendicular\$3 or cross\$3 or interlac\$3 or intertwin\$3)) and semiconduct\$3 and (stor\$3 or capacit\$4)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2002/11/21 13:55
-	541	((photoresist or resist or photopolymer\$7) and (etch or etched or etching or etchant) and ((doubl\$3 or plural\$4) same expos\$) same (perpendicular\$3 or cross\$3 or interlac\$3 or intertwin\$3)) and semiconduct\$3 and (stor\$3 or capacit\$4)) and ((line\$2 or parallel) same expos\$3)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2002/11/21 13:56
-	398	((((photoresist or resist or photopolymer\$7) and (etch or etched or etching or etchant) and ((doubl\$3 or plural\$4) same expos\$) same (perpendicular\$3 or cross\$3 or interlac\$3 or intertwin\$3)) and semiconduct\$3 and (stor\$3 or capacit\$4)) and ((line\$2 or parallel) same expos\$3)) and develop\$4	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2002/11/21 13:56
-	66	(((((photoresist or resist or photopolymer\$7) and (etch or etched or etching or etchant) and ((doubl\$3 or plural\$4) same expos\$) same (perpendicular\$3 or cross\$3 or interlac\$3 or intertwin\$3)) and semiconduct\$3 and (stor\$3 or capacit\$4)) and ((line\$2 or parallel) same expos\$3)) and develop\$4) and (dynamic adj random adj access or DRAM)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2002/11/21 13:57

-	769	((photoresist or resist or photopolymer\$7) and (etch or etched or etching or etchant) and ((doubl\$3 or plural\$4) same expos\$) same (perpendicular\$3 or cross\$3 or interlac\$3 or intertwin\$3)) and semiconduct\$3 and (stor\$3 or capacit\$4 or memor\$5)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2002/11/21 13:56
-	602	((photoresist or resist or photopolymer\$7) and (etch or etched or etching or etchant) and ((doubl\$3 or plural\$4) same expos\$) same (perpendicular\$3 or cross\$3 or interlac\$3 or intertwin\$3)) and semiconduct\$3 and (stor\$3 or capacit\$4 or memor\$5)) and ((line\$2 or parallel) same expos\$3)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2002/11/21 13:56
-	438	((photoresist or resist or photopolymer\$7) and (etch or etched or etching or etchant) and ((doubl\$3 or plural\$4) same expos\$) same (perpendicular\$3 or cross\$3 or interlac\$3 or intertwin\$3)) and semiconduct\$3 and (stor\$3 or capacit\$4 or memor\$5)) and ((line\$2 or parallel) same expos\$3)) and develop\$4	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2002/11/21 13:57
-	74	((photoresist or resist or photopolymer\$7) and (etch or etched or etching or etchant) and ((doubl\$3 or plural\$4) same expos\$) same (perpendicular\$3 or cross\$3 or interlac\$3 or intertwin\$3)) and semiconduct\$3 and (stor\$3 or capacit\$4 or memor\$5)) and ((line\$2 or parallel) same expos\$3)) and develop\$4) and (dynamic adj random adj access or DRAM)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2002/11/22 11:52
-	331	((photoresist or resist or photopolymer\$7) and (etch or etched or etching or etchant) and ((doubl\$3 or plural\$4) same expos\$) same (perpendicular\$3 or cross\$3 or interlac\$3 or intertwin\$3 or row or column)) and semiconduct\$3 and (stor\$3 or capacit\$4 or memor\$5)) and ((line\$2 or parallel) same expos\$3)) and develop\$4) and (dynamic adj random adj access or DRAM or memory)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2002/11/22 11:55
-	62	((photoresist or resist or photopolymer\$7) and (etch or etched or etching or etchant) and ((doubl\$3 or plural\$4) same expos\$) same (perpendicular\$3 or cross\$3 or interlac\$3 or intertwin\$3 or row or column)) and semiconduct\$3 and (stor\$3 or capacit\$4 or memor\$5)) and ((line\$2 or parallel) same expos\$3)) and develop\$4) and (dynamic adj random adj access or DRAM or memory)) and ((round\$3 with corner) or (optical with proximity) or (line with short\$5))	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2002/11/22 13:35
-	4	((photoresist or resist or photopolymer\$7) and (etch or etched or etching or etchant) and ((doubl\$3 or plural\$4) same expos\$) same (perpendicular\$3 or cross\$3 or interlac\$3 or intertwin\$3 or row or column)) and semiconduct\$3 and (stor\$3 or capacit\$4 or memor\$5)) and ((line\$2 or parallel) same expos\$3)) and develop\$4) and (dynamic adj random adj access or DRAM or memory)) and ((round\$3 with corner) or (optical with proximity) or (line with short\$5))) and 430/312.ccls.	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/02/10 18:19

-	2	(((((((photoresist or resist or photopolymer\$7) and (etch or etched or etching or etchant) and ((doubl\$3 or plural\$4) same expos\$) same (perpendicular\$3 or cross\$3 or interlac\$3 or intertwin\$3 or row or column)) and semiconduct\$3 and (stor\$3 or capacit\$4 or memor\$5)) and ((line\$2 or parallel) same expos\$3)) and develop\$4) and (dynamic adj random adj access or DRAM or memory)) and ((round\$3 with corner) or (optical with proximity) or (line with short\$5))) and 430/394.ccls.	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/02/10 18:22
-	3	(((((((photoresist or resist or photopolymer\$7) and (etch or etched or etching or etchant) and ((doubl\$3 or plural\$4) same expos\$) same (perpendicular\$3 or cross\$3 or interlac\$3 or intertwin\$3 or row or column)) and semiconduct\$3 and (stor\$3 or capacit\$4 or memor\$5)) and ((line\$2 or parallel) same expos\$3)) and develop\$4) and (dynamic adj random adj access or DRAM or memory)) and ((round\$3 with corner) or (optical with proximity) or (line with short\$5))) and 430/313.ccls.	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/02/10 18:23
-	3	(((((((photoresist or resist or photopolymer\$7) and (etch or etched or etching or etchant) and ((doubl\$3 or plural\$4) same expos\$) same (perpendicular\$3 or cross\$3 or interlac\$3 or intertwin\$3 or row or column)) and semiconduct\$3 and (stor\$3 or capacit\$4 or memor\$5)) and ((line\$2 or parallel) same expos\$3)) and develop\$4) and (dynamic adj random adj access or DRAM or memory)) and ((round\$3 with corner) or (optical with proximity) or (line with short\$5))) and 430/311.ccls.	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/02/10 18:24

-	57	<p>((((photoresist or resist or photopolymer\$7) and (etch or etched or etching or etchant) and ((doubl\$3 or plural\$4) same expos\$) same (perpendicular\$3 or cross\$3 or interlac\$3 or intertwin\$3 or row or column)) and semiconduct\$3 and (stor\$3 or capacit\$4 or memor\$5)) and ((line\$2 or parallel) same expos\$3)) and develop\$4) and (dynamic adj random adj access or DRAM or memory)) and ((round\$3 with corner) or (optical with proximity) or (line with short\$5)) not ((((((photoresist or resist or photopolymer\$7) and (etch or etched or etching or etchant) and ((doubl\$3 or plural\$4) same expos\$) same (perpendicular\$3 or cross\$3 or interlac\$3 or intertwin\$3 or row or column)) and semiconduct\$3 and (stor\$3 or capacit\$4 or memor\$5)) and ((line\$2 or parallel) same expos\$3)) and develop\$4) and (dynamic adj random adj access or DRAM or memory)) and ((round\$3 with corner) or (optical with proximity) or (line with short\$5))) and 430/312.ccls.) not ((((((photoresist or resist or photopolymer\$7) and (etch or etched or etching or etchant) and ((doubl\$3 or plural\$4) same expos\$) same (perpendicular\$3 or cross\$3 or interlac\$3 or intertwin\$3 or row or column)) and semiconduct\$3 and (stor\$3 or capacit\$4 or memor\$5)) and ((line\$2 or parallel) same expos\$3)) and develop\$4) and (dynamic adj random adj access or DRAM or memory)) and ((round\$3 with corner) or (optical with proximity) or (line with short\$5))) and 430/394.ccls.) not ((((((photoresist or resist or photopolymer\$7) and (etch or etched or etching or etchant) and ((doubl\$3 or plural\$4) same expos\$) same (perpendicular\$3 or cross\$3 or interlac\$3 or intertwin\$3 or row or column)) and semiconduct\$3 and (stor\$3 or capacit\$4 or memor\$5)) and ((line\$2 or parallel) same expos\$3)) and develop\$4) and (dynamic adj random adj access or DRAM or memory)) and ((round\$3 with corner) or (optical with proximity) or (line with short\$5))) and 430/313.ccls.) not ((((((photoresist or resist or photopolymer\$7) and (etch or etched or etching or etchant) and ((doubl\$3 or plural\$4) same expos\$) same (perpendicular\$3 or cross\$3 or interlac\$3 or intertwin\$3 or row or column)) and semiconduct\$3 and (stor\$3 or capacit\$4 or memor\$5)) and ((line\$2 or parallel) same expos\$3)) and develop\$4) and (dynamic adj random adj access or DRAM or memory)) and ((round\$3 with corner) or (optical with proximity) or (line with short\$5))) and 430/311.ccls.)</p>	<p>USPAT; US-PGPUB; EPO; JPO; IBM_TDB</p>	2003/02/10 18:26
-	5004	430/311-313,394.ccls.	<p>USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB</p>	2002/12/04 10:24

-	1	<p>(430/311-313,394.ccls. and (interlac\$ or intertwin\$ or double adj expos\$)) not ((((((photoresist or resist or photopolymer\$7) and (etch or etched or etching or etchant) and ((doubl\$3 or plural\$4) same expos\$) same (perpendicular\$3 or cross\$3 or interlac\$3 or intertwin\$3 or row or column)) and semiconduct\$3 and (stor\$3 or capacit\$4 or memor\$5)) and ((line\$2 or parallel) same expos\$3)) and develop\$4) and (dynamic adj random adj access or DRAM or memory)) and ((round\$3 with corner) or (optical with proximity) or (line with short\$5)) not ((((((photoresist or resist or photopolymer\$7) and (etch or etched or etching or etchant) and ((doubl\$3 or plural\$4) same expos\$) same (perpendicular\$3 or cross\$3 or interlac\$3 or intertwin\$3 or row or column)) and semiconduct\$3 and (stor\$3 or capacit\$4 or memor\$5)) and ((line\$2 or parallel) same expos\$3)) and develop\$4) and (dynamic adj random adj access or DRAM or memory)) and ((round\$3 with corner) or (optical with proximity) or (line with short\$5))) and 430/312.ccls.) not ((((((photoresist or resist or photopolymer\$7) and (etch or etched or etching or etchant) and ((doubl\$3 or plural\$4) same expos\$) same (perpendicular\$3 or cross\$3 or interlac\$3 or intertwin\$3 or row or column)) and semiconduct\$3 and (stor\$3 or capacit\$4 or memor\$5)) and ((line\$2 or parallel) same expos\$3)) and develop\$4) and (dynamic adj random adj access or DRAM or memory)) and ((round\$3 with corner) or (optical with proximity) or (line with short\$5))) and 430/394.ccls.) not ((((((photoresist or resist or photopolymer\$7) and (etch or etched or etching or etchant) and ((doubl\$3 or plural\$4) same expos\$) same (perpendicular\$3 or cross\$3 or interlac\$3 or intertwin\$3 or row or column)) and semiconduct\$3 and (stor\$3 or capacit\$4 or memor\$5)) and ((line\$2 or parallel) same expos\$3)) and develop\$4) and (dynamic adj random adj access or DRAM or memory)) and ((round\$3 with corner) or (optical with proximity) or (line with short\$5))) and 430/313.ccls.) not ((((((photoresist or resist or photopolymer\$7) and (etch or etched or etching or etchant) and ((doubl\$3 or plural\$4) same expos\$) same (perpendicular\$3 or cross\$3 or interlac\$3 or intertwin\$3 or row or column)) and semiconduct\$3 and (stor\$3 or capacit\$4 or memor\$5)) and ((line\$2 or parallel) same expos\$3)) and develop\$4) and (dynamic adj random adj access or DRAM or memory)) and ((round\$3 with corner) or (optical with proximity) or (line with short\$5))) and 430/311.ccls.))</p> <p>430/312,394.ccls.</p>	<p>USPAT; US-PGPUB; EPO; JPO; IBM_TDB</p>	2002/12/04 10:03
-	2009		<p>USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB</p>	2002/12/04 10:27

-	324	430/312,394.cor.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB USPÄT	2003/02/10 18:34
-	13	("4591540" "5286584" "5308741" "5340700" "5424154" "5532090" "5563012" "5620816" "5702868" "5804339" "5807649" "5851707" "5863677").PN.	USPÄT	2002/12/04 12:36
-	1685	430/312,394.ccls. not 430/312,394.cor.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB USPÄT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2003/02/10 18:51
-	2995	430/311-313,394.ccls. not 430/312,394.ccls. not 430/312,394.cor.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2003/02/10 19:12
-	2	((("5103274") or ("5120671"))).PN.	USPAT; US-PGPUB	2002/12/07 14:02
-	3	((("6184151") or ("5955244") or ("20010028422"))).PN.	USPAT; US-PGPUB	2002/12/10 14:44